

EV318284425

Inventor: Garo J. Derderian et al.

Title: Methods of Depositing a Silicon Dioxide Comprising Layer in the
Fabrication of Integrated Circuitry, and a Method of Forming Trench
Isolation in the Fabrication of Integrated Circuitry

Assignee: Micron Technology, Inc.

INFORMATION DISCLOSURE STATEMENT

References -- See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with
37 CFR § 1.56. Copies of the cited art are included. No admission is made
regarding whether all the submitted references are prior art.

Respectfully submitted,

Dated: 9-5-03

Attorney: 

Mark S. Matkin
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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2307		SERIAL NO. Unknown		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Garo J. Derderian et al.				
				FILING DATE Filed Herewith		GROUP Unknown		
U.S. PATENT DOCUMENTS								
*Examiner's Initials		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	6,300,219 B1	10/09/01	Doan et al.				
	AB	6,534,395 B2	03/18/03	Werkhoven et al.				
	AC	10/615,051		Vaartstra (as filed)			07/07/2003	
	AD							
	AE							
	AF							
	AG							
	AH							
	AI							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AJ	WO 02/27063 A2	04.04.02	WIPO (Harward College)				
	AK							
	AL							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AM		Hausmann et al., <i>Rapid Vapor Deposition of Highly Conformal Silica Nanolaminates</i> , 298 SCIENCE 402-406					
			(October 11, 2002)					
	AN		Klaus et al., <i>Atomic Layer Deposition of SiO₂ Using Catalyzed and Uncatalyzed Self-Limiting Surface</i>					
			<i>Reactions</i> , 6 SURFACE REVIEW AND LETTERS, Nos. 3 and 4, pp. 435-448 (1999).					
	AO		Miller et al., <i>Self-limiting chemical vapor deposition of an ultra-thin silicon oxide film using tri-(tert-butoxy)</i>					
			<i>Silanol</i> , 397 THIN SOLID FILMS 78-82 (2001).					
EXAMINER		DATE CONSIDERED						
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								